

Do Not Remove!

chain nodes :

18 19 20 21 22 23 24 25 26 27 28 29 30 31 32 33 34 35 36 37 38 39 40  
41 42 43 44 45 46 47 48 53 55 56

ring nodes :

1 2 3 4 5 6 7 8 9 10 11 12 13 14 15 16 17

chain bonds :

1-33 4-18 5-28 8-31 9-56 12-55 13-19 14-27 15-20 15-30 20-21 20-22 20-29 22-23  
23-24 24-25 24-26 25-53 32-41 32-42 32-43 33-34 34-35 34-36 37-38 38-39 38-40  
44-45 44-46 45-47 47-48

ring bonds :

1-2 1-6 2-3 3-4 4-5 4-7 5-6 5-10 7-8 7-11 8-9 8-14 9-10 11-12 12-13 13-14  
13-15 14-17 15-16 16-17

exact/norm bonds :

1-2 1-6 1-33 2-3 3-4 4-5 4-7 5-6 5-10 7-8 7-11 8-9 8-14 9-10 9-56 11-12  
12-13 12-55 13-14 13-15 14-17 15-16 16-17 24-25 24-26 25-53 33-34 34-36 37-38  
38-40 44-45

exact bonds :

4-18 5-28 8-31 13-19 14-27 15-20 15-30 20-21 20-22 20-29 22-23 23-24 32-41  
32-42 32-43 34-35 38-39 44-46 45-47 47-48

G1:[\*1],[\*2]

G2:H,[\*3]

Match level :

1:Atom 2:Atom 3:Atom 4:Atom 5:Atom 6:Atom 7:Atom 8:Atom 9:Atom 10:Atom 11:Atom  
12:Atom 13:Atom 14:Atom 15:Atom 16:Atom 17:Atom 18:CLASS 19:CLASS 20:CLASS  
21:CLASS 22:CLASS 23:CLASS 24:CLASS 25:CLASS 26:CLASS 27:CLASS 28:CLASS 29:CLASS  
30:CLASS 31:CLASS 32:CLASS 33:CLASS 34:CLASS 35:CLASS 36:CLASS 37:CLASS 38:CLASS  
39:CLASS 40:CLASS 41:CLASS 42:CLASS 43:CLASS 44:CLASS 45:CLASS 46:CLASS 47:CLASS  
48:CLASS 53:CLASS 55:CLASS 56:CLASS

Stereo Bonds:

18-4 (Single wedge).  
19-13 (Single wedge).

Stereo Chiral Centers:

4 (Parity=Even)  
13 (Parity=Even)

Stereo RSS Sets:

Type=Relative (Default). 2 Nodes= 4 13

\* \* \* \* \* STN Columbus \* \* \* \* \*

FILE 'HOME' ENTERED AT 14:37:54 ON 13 MAY 2003

=> file reg		
COST IN U.S. DOLLARS	SINCE FILE	TOTAL
	ENTRY	SESSION
FULL ESTIMATED COST	0.21	0.21

FILE 'REGISTRY' ENTERED AT 14:37:59 ON 13 MAY 2003  
USE IS SUBJECT TO THE TERMS OF YOUR STN CUSTOMER AGREEMENT.  
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provided by InfoChem.

STRUCTURE FILE UPDATES: 12 MAY 2003 HIGHEST RN 514787-04-3  
DICTIONARY FILE UPDATES: 12 MAY 2003 HIGHEST RN 514787-04-3

TSCA INFORMATION NOW CURRENT THROUGH JANUARY 6, 2003

Please note that search-term pricing does apply when  
conducting SmartSELECT searches.

Crossover limits have been increased. See HELP CROSSOVER for details.

Experimental and calculated property data are now available. See HELP  
PROPERTIES for more information. See STNote 27, Searching Properties  
in the CAS Registry File, for complete details:  
<http://www.cas.org/ONLINE/STN/STNOTES/stnotes27.pdf>

=> ....Testing the current file.... screen

ENTER SCREEN EXPRESSION OR (END):end

=> screen 966 AND 1006 AND 1051

L1 SCREEN CREATED

=> screen 1821 OR 1822 OR 1823 OR 1824

L2 SCREEN CREATED

=>  
Uploading C:\Program Files\Stnexp\Queries\09878803.str

L3 STRUCTURE UPLOADED

=> que L3 AND L1 AND L2

L4 QUE L3 AND L1 AND L2

=> d  
L4 HAS NO ANSWERS  
L1 SCR 966 AND 1006 AND 1051  
L2 SCR 1821 OR 1822 OR 1823 OR 1824  
L3 STR

\* STRUCTURE DIAGRAM TOO LARGE FOR DISPLAY - AVAILABLE VIA OFFLINE PRINT \*



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Property values tagged with IC are from the ZIC/VINITI data file  
provided by InfoChem.

STRUCTURE FILE UPDATES: 12 MAY 2003 HIGHEST RN 514787-04-3  
DICTIONARY FILE UPDATES: 12 MAY 2003 HIGHEST RN 514787-04-3

TSCA INFORMATION NOW CURRENT THROUGH JANUARY 6, 2003

Please note that search-term pricing does apply when  
conducting SmartSELECT searches.

Crossover limits have been increased. See HELP CROSSOVER for details.

Experimental and calculated property data are now available. See HELP  
PROPERTIES for more information. See STNote 27, Searching Properties  
in the CAS Registry File, for complete details:  
<http://www.cas.org/ONLINE/STN/STNOTES/stnotes27.pdf>

=> ....Testing the current file.... screen

ENTER SCREEN EXPRESSION OR (END):end

=> screen 966 AND 1006

L8 SCREEN CREATED

=> screen 1821 OR 1822 OR 1823 OR 1824

L9 SCREEN CREATED

=>  
Uploading C:\Program Files\Stnexp\Queries\09878803.str

L10 STRUCTURE UPLOADED

=> que L10 AND L8 AND L9

L11 QUE L10 AND L8 AND L9

=> s l11 sss sam  
SAMPLE SEARCH INITIATED 14:41:31 FILE 'REGISTRY'  
SAMPLE SCREEN SEARCH COMPLETED - 57 TO ITERATE

100.0% PROCESSED 57 ITERATIONS 0 ANSWERS  
SEARCH TIME: 00.00.01

FULL FILE PROJECTIONS: ONLINE \*\*COMPLETE\*\*  
BATCH \*\*COMPLETE\*\*  
PROJECTED ITERATIONS: 688 TO 1592  
PROJECTED ANSWERS: 0 TO 0

L12 0 SEA SSS SAM L10 AND L8 AND L9

=> FIL CAPLUS ZCAPLUS HCAPLUS CSCHM EUROPATFULL FEDREGFULL IFIPAT JAPIO		
COST IN U.S. DOLLARS	SINCE FILE	TOTAL
	ENTRY	SESSION
FULL ESTIMATED COST	0.40	7.25

FILE 'CAPLUS' ENTERED AT 14:41:37 ON 13 MAY 2003  
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FILE 'ZCAPLUS' ENTERED AT 14:41:37 ON 13 MAY 2003  
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FILE 'HCAPLUS' ENTERED AT 14:41:37 ON 13 MAY 2003  
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FILE 'CSCHEM' ENTERED AT 14:41:37 ON 13 MAY 2003  
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FILE 'EUROPATFULL' ENTERED AT 14:41:37 ON 13 MAY 2003  
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FILE 'FEDREGFULL' ENTERED AT 14:41:37 ON 13 MAY 2003  
COPYRIGHT (C) 2003 U.S. Govt Printing Office (USGPO)

FILE 'IFIPAT' ENTERED AT 14:41:37 ON 13 MAY 2003  
COPYRIGHT (C) 2003 IFI CLAIMS(R) Patent Services (IFI)

FILE 'JAPIO' ENTERED AT 14:41:37 ON 13 MAY 2003  
COPYRIGHT (C) 2003 Japanese Patent Office (JPO)- JAPIO

=> s ;12  
ENTER LOGIC EXPRESSION, QUERY NAME, OR (END):112  
SUBSTANCE QUERIES NOT VALID IN THIS FILE  
SUBSTANCE QUERIES NOT VALID IN THIS FILE  
COMMAND STACK INTERRUPTED. ENTER "DISPLAY HISTORY"  
TO SEE WHICH COMMANDS WERE EXECUTED.

The logic expression entered contains L#s or saved query names which correspond to structures built by the STRUCTURE command or to screen sets. These must be searched in a substance file such as the REGISTRY file. In some files you may use a Registry Number answer set from a structure search as a search term or profile in some bibliographic file containing Registry Numbers, e.g. the CA file. For an explanation, enter "HELP CROSSOVER" at an arrow prompt (=>).

=> d his

(FILE 'HOME' ENTERED AT 14:37:54 ON 13 MAY 2003)

FILE 'REGISTRY' ENTERED AT 14:37:59 ON 13 MAY 2003

L1 SCREEN 966 AND 1006 AND 1051  
L2 SCREEN 1821 OR 1822 OR 1823 OR 1824  
L3 STRUCTURE UPLOADED  
L4 QUE L3 AND L1 AND L2  
L5 0 S L4 SSS SAM

FILE 'CAPLUS, HCAPLUS, USPATFULL, USPAT2' ENTERED AT 14:38:52 ON 13 MAY 2003

L6 0 S L5  
L7 0 S L5

FILE 'HOME' ENTERED AT 14:39:13 ON 13 MAY 2003

FILE 'REGISTRY' ENTERED AT 14:41:05 ON 13 MAY 2003

L8 SCREEN 966 AND 1006  
L9 SCREEN 1821 OR 1822 OR 1823 OR 1824

L10               STRUCTURE UPLOADED  
L11               QUE L10 AND L8 AND L9  
L12               0 S L11 SSS SAM

FILE 'CAPLUS, ZCAPLUS, HCAPLUS, CSCHM, EUROPATFULL, FEDREGFULL, IFIPAT,  
JAPIO' ENTERED AT 14:41:37 ON 13 MAY 2003

=> s l12

SUBSTANCE QUERIES NOT VALID IN THIS FILE

SUBSTANCE QUERIES NOT VALID IN THIS FILE

The logic expression entered contains L#s or saved query names which correspond to structures built by the STRUCTURE command or to screen sets. These must be searched in a substance file such as the REGISTRY file. In some files you may use a Registry Number answer set from a structure search as a search term or profile in some bibliographic file containing Registry Numbers, e.g. the CA file. For an explanation, enter "HELP CROSSOVER" at an arrow prompt (=>).

=> FIL CAPLUS HCAPLUS USPATFULL USPAT2  
COST IN U.S. DOLLARS

SINCE FILE	TOTAL
ENTRY	SESSION
8.64	15.89

FULL ESTIMATED COST

FILE 'CAPLUS' ENTERED AT 14:42:14 ON 13 MAY 2003  
USE IS SUBJECT TO THE TERMS OF YOUR STN CUSTOMER AGREEMENT.  
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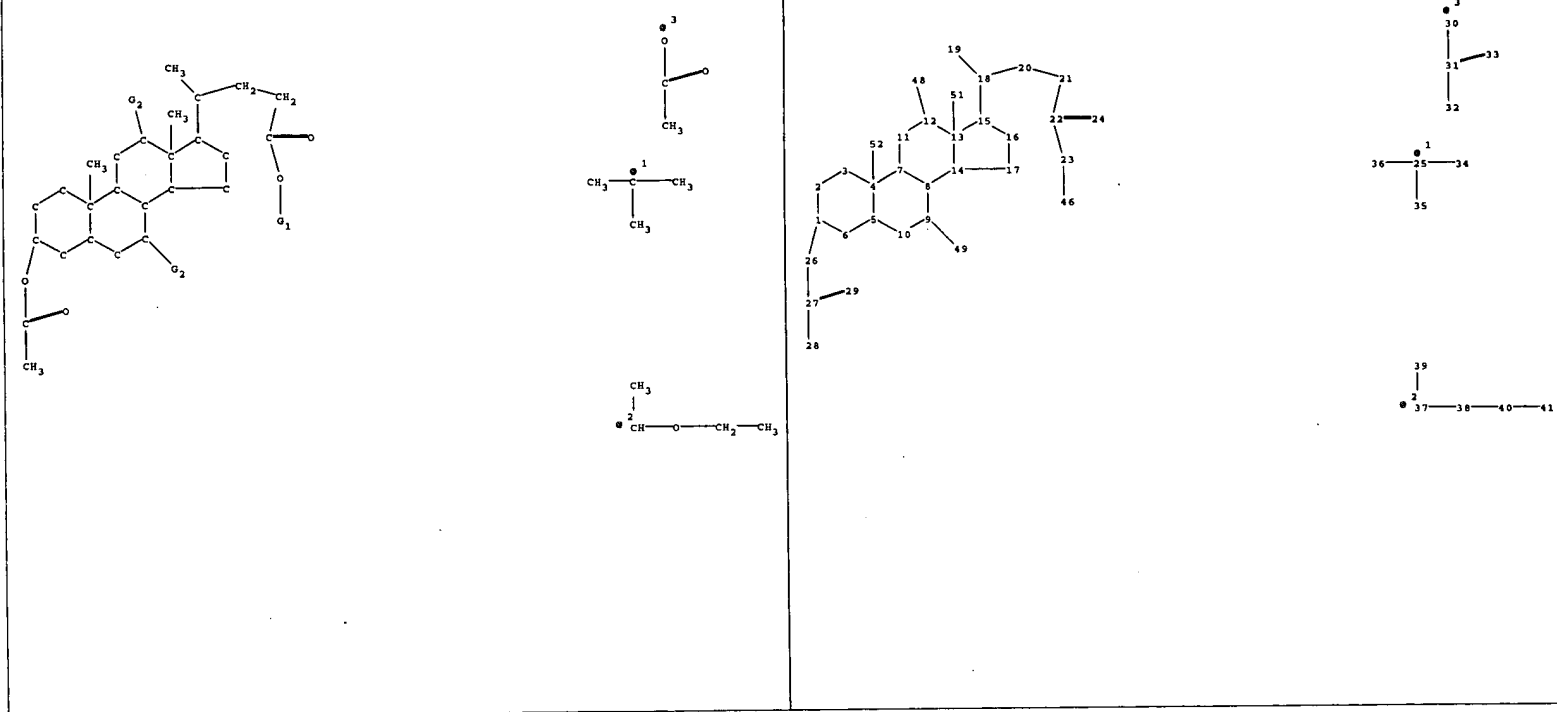
FILE 'HCAPLUS' ENTERED AT 14:42:14 ON 13 MAY 2003  
USE IS SUBJECT TO THE TERMS OF YOUR STN CUSTOMER AGREEMENT.  
PLEASE SEE "HELP USAGETERMS" FOR DETAILS.  
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FILE 'USPATFULL' ENTERED AT 14:42:14 ON 13 MAY 2003  
CA INDEXING COPYRIGHT (C) 2003 AMERICAN CHEMICAL SOCIETY (ACS)

FILE 'USPAT2' ENTERED AT 14:42:14 ON 13 MAY 2003  
CA INDEXING COPYRIGHT (C) 2003 AMERICAN CHEMICAL SOCIETY (ACS)

=> s l12

L13               0 L12



chain nodes :  
 18 19 20 21 22 23 24 25 26 27 28 29 30 31 32 33 34 35 36 37 38 39 40  
 41 46 48 49 51 52

ring nodes :  
 1 2 3 4 5 6 7 8 9 10 11 12 13 14 15 16 17

chain bonds :  
 1-26 4-52 9-49 12-48 13-51 15-18 18-19 18-20 20-21 21-22 22-23 22-24 23-46  
 25-34 25-35 25-36 26-27 27-28 27-29 30-31 31-32 31-33 37-38 37-39 38-40 40-41

ring bonds :  
 1-2 1-6 2-3 3-4 4-5 4-7 5-6 5-10 7-8 7-11 8-9 8-14 9-10 11-12 12-13 13-14  
 13-15 14-17 15-16 16-17

exact/norm bonds :  
 1-2 1-6 1-26 2-3 3-4 4-5 4-7 5-6 5-10 7-8 7-11 8-9 8-14 9-10 9-49 11-12  
 12-13 12-48 13-14 13-15 14-17 15-16 16-17 22-23 22-24 23-46 26-27 27-29 30-31  
 31-33 37-38

exact bonds :  
 4-52 13-51 15-18 18-19 18-20 20-21 21-22 25-34 25-35 25-36 27-28 31-32 37-39  
 38-40 40-41

G1:[\*1],[\*2]

G2:H,[\*3]

Match level :

1:Atom 2:Atom 3:Atom 4:Atom 5:Atom 6:Atom 7:Atom 8:Atom 9:Atom 10:Atom 11:Atom  
 12:Atom 13:Atom 14:Atom 15:Atom 16:Atom 17:Atom 18:CLASS 19:CLASS 20:CLASS  
 21:CLASS 22:CLASS 23:CLASS 24:CLASS 25:CLASS 26:CLASS 27:CLASS 28:CLASS 29:CLASS  
 30:CLASS 31:CLASS 32:CLASS 33:CLASS 34:CLASS 35:CLASS 36:CLASS 37:CLASS 38:CLASS  
 39:CLASS 40:CLASS 41:CLASS 46:CLASS 48:CLASS 49:CLASS 51:CLASS 52:CLASS



=> s 19 sss sam  
SAMPLE SEARCH INITIATED 15:48:08 FILE 'REGISTRY'  
SAMPLE SCREEN SEARCH COMPLETED - 77 TO ITERATE

100.0% PROCESSED 77 ITERATIONS 7 ANSWERS  
SEARCH TIME: 00.00.01

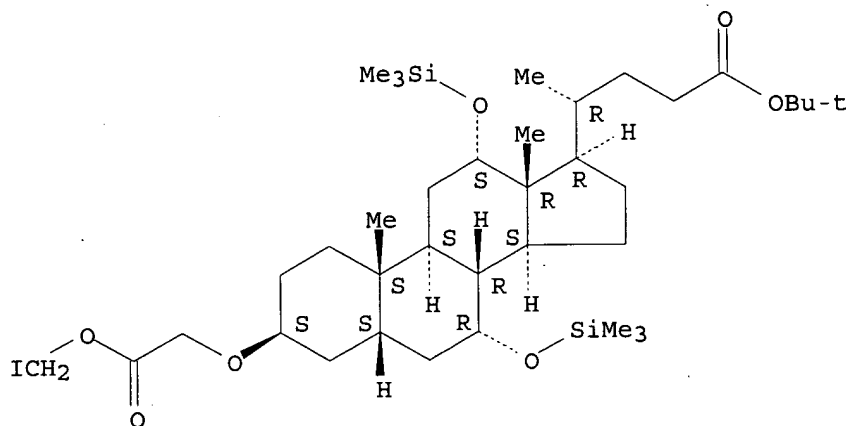
FULL FILE PROJECTIONS: ONLINE \*\*COMPLETE\*\*  
BATCH \*\*COMPLETE\*\*  
PROJECTED ITERATIONS: 1014 TO 2066  
PROJECTED ANSWERS: 7 TO 298

L10 7 SEA SSS SAM L8 AND L6 AND L7

=> d

L10 ANSWER 1 OF 7 REGISTRY COPYRIGHT 2003 ACS  
RN 433951-25-8 REGISTRY  
CN Cholan-24-oic acid, 3-[2-(iodomethoxy)-2-oxoethoxy]-7,12-  
bis[(trimethylsilyl)oxy]-, 1,1-dimethylethyl ester,  
(3.beta.,5.beta.,7.alpha.,12.alpha.)- (9CI) (CA INDEX NAME)  
FS STEREOSEARCH  
MF C37 H67 I O7 Si2  
SR CA  
LC STN Files: CA, CAPLUS

Absolute stereochemistry.



\*\*PROPERTY DATA AVAILABLE IN THE 'PROP' FORMAT\*\*

1 REFERENCES IN FILE CA (1957 TO DATE)  
1 REFERENCES IN FILE CAPLUS (1957 TO DATE)

=> FIL CAPLUS HCAPLUS USPATFULL USPAT2  
COST IN U.S. DOLLARS  
FULL ESTIMATED COST

SINCE FILE	TOTAL
ENTRY	SESSION
2.08	3.74

FILE 'CAPLUS' ENTERED AT 15:48:34 ON 13 MAY 2003  
USE IS SUBJECT TO THE TERMS OF YOUR STN CUSTOMER AGREEMENT.  
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FILE 'HCAPLUS' ENTERED AT 15:48:34 ON 13 MAY 2003  
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FILE 'USPATFULL' ENTERED AT 15:48:34 ON 13 MAY 2003  
CA INDEXING COPYRIGHT (C) 2003 AMERICAN CHEMICAL SOCIETY (ACS)

FILE 'USPAT2' ENTERED AT 15:48:34 ON 13 MAY 2003  
CA INDEXING COPYRIGHT (C) 2003 AMERICAN CHEMICAL SOCIETY (ACS)

=> d his

(FILE 'HOME' ENTERED AT 15:44:07 ON 13 MAY 2003)

FILE 'REGISTRY' ENTERED AT 15:44:16 ON 13 MAY 2003

L1 SCREEN 965  
L2 SCREEN 1821 OR 1822 OR 1823 OR 1824  
L3 STRUCTURE UPLOADED  
L4 QUE L3 AND L1 AND L2  
L5 50 S L4 SSS SAM

FILE 'HOME' ENTERED AT 15:45:01 ON 13 MAY 2003

FILE 'REGISTRY' ENTERED AT 15:47:45 ON 13 MAY 2003

L6 SCREEN 965  
L7 SCREEN 1821 OR 1822 OR 1823 OR 1824  
L8 STRUCTURE UPLOADED  
L9 QUE L8 AND L6 AND L7  
L10 7 S L9 SSS SAM

FILE 'CAPLUS, HCAPLUS, USPATFULL, USPAT2' ENTERED AT 15:48:34 ON 13 MAY 2003

=> s l10

L11 12 L10

=> duplicates remove l11

DUPLICATE PREFERENCE IS 'CAPLUS, HCAPLUS, USPATFULL'  
KEEP DUPLICATES FROM MORE THAN ONE FILE? Y/(N):n  
PROCESSING COMPLETED FOR L11

L12 7 DUPLICATE REMOVE L11 (5 DUPLICATES REMOVED)

=> d l12 1-7 ibib hitstr

L12 ANSWER 1 OF 7 CAPLUS COPYRIGHT 2003 ACS DUPLICATE 1  
ACCESSION NUMBER: 2002:429031 CAPLUS  
DOCUMENT NUMBER: 137:20509  
TITLE: Preparation and formulation of bile-acid derived  
compounds for enhancing oral absorption and systemic  
bioavailability of drugs  
INVENTOR(S): Gallop, Mark A.; Cundy, Kenneth C.  
PATENT ASSIGNEE(S): Xenoport, Inc., USA  
SOURCE: PCT Int. Appl., 185 pp.  
CODEN: PIXXD2  
DOCUMENT TYPE: Patent  
LANGUAGE: English  
FAMILY ACC. NUM. COUNT: 9  
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
WO 2002044324	A2	20020606	WO 2001-US42612	20011005
W: AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BY, BZ, CA, CH, CN,				

CO, CR, CU, CZ, DE, DK, DM, DZ, EC, EE, ES, FI, GB, GD, GE, GH,  
 GM, HR, HU, ID, IL, IN, IS, JP, KE, KG, KP, KR, KZ, LC, LK, LR,  
 LS, LT, LU, LV, MA, MD, MG, MK, MN, MW, MX, MZ, NO, NZ, PH, PL,  
 PT, RO, RU, SD, SE, SG, SI, SK, SL, TJ, TM, TR, TT, TZ, UA, UG,  
 US, UZ, VN, YU, ZA, ZW, AM, AZ, BY, KG, KZ, MD, RU, TJ, TM  
 RW: GH, GM, KE, LS, MW, MZ, SD, SL, SZ, TZ, UG, ZW, AT, BE, CH, CY,  
 DE, DK, ES, FI, FR, GB, GR, IE, IT, LU, MC, NL, PT, SE, TR, BF,  
 BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE, SN, TD, TG

AU 2002043204 A5 20020611 AU 2002-43204 20011005

US 2002099041 A1 20020725 US 2001-972411 20011005

PRIORITY APPLN. INFO.:

US 2000-238758P P 20001006

WO 2001-US42612 W 20011005

OTHER SOURCE(S): MARPAT 137:20509

IT 433951-17-8P 433951-22-5P 433951-25-8P

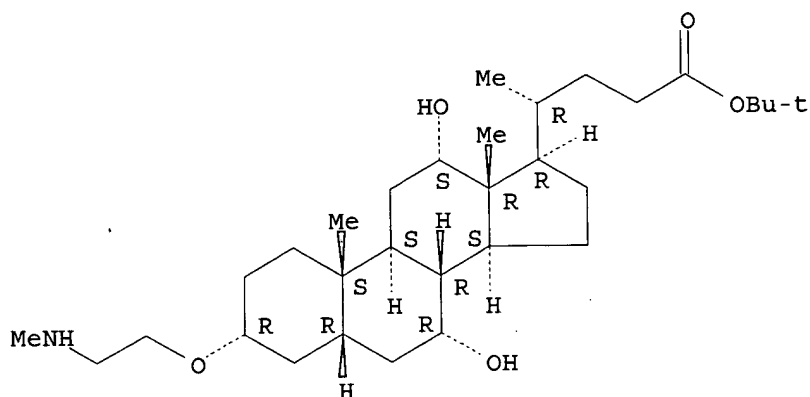
RL: RCT (Reactant); SPN (Synthetic preparation); PREP (Preparation); RACT  
 (Reactant or reagent)

(prepn. and formulation of bile-acid derived compds. for enhancing oral  
 absorption and systemic bioavailability of drugs)

RN 433951-17-8 CAPLUS

CN Cholan-24-oic acid, 7,12-dihydroxy-3-[2-(methylamino)ethoxy]-,  
 1,1-dimethylethyl ester, (3.alpha.,5.beta.,7.alpha.,12.alpha.)- (9CI) (CA  
 INDEX NAME)

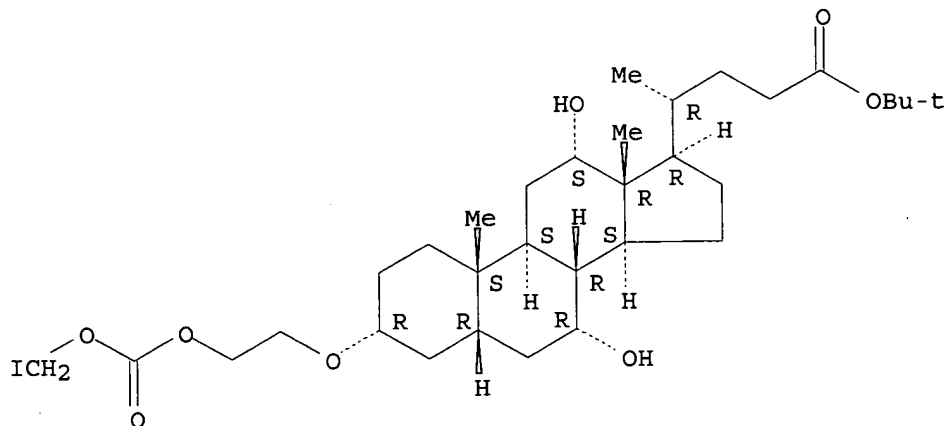
Absolute stereochemistry.



RN 433951-22-5 CAPLUS

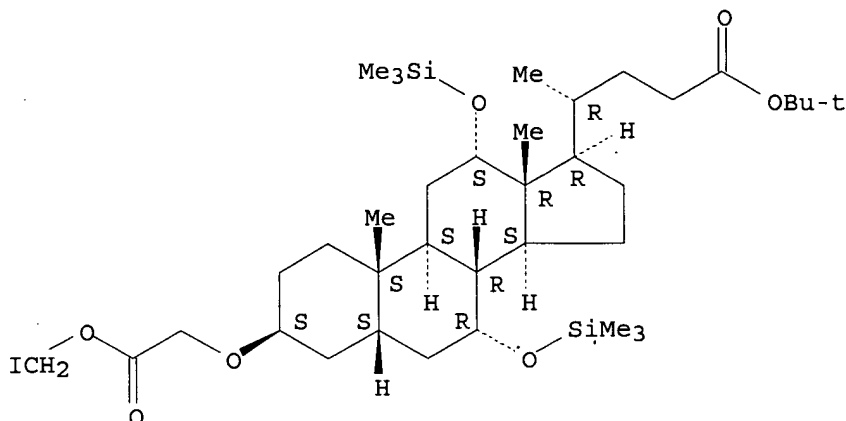
CN Cholan-24-oic acid, 7,12-dihydroxy-3-[2-[[[(iodomethoxy)carbonyl]oxy]ethoxy]  
 ]-, 1,1-dimethylethyl ester, (3.alpha.,5.beta.,7.alpha.,12.alpha.)- (9CI)  
 (CA INDEX NAME)

Absolute stereochemistry.



RN 433951-25-8 CAPLUS  
 CN Cholan-24-oic acid, 3-[2-(iodomethoxy)-2-oxoethoxy]-7,12-bis[(trimethylsilyl)oxy]-, 1,1-dimethylethyl ester, (3.beta.,5.beta.,7.alpha.,12.alpha.)- (9CI) (CA INDEX NAME)

Absolute stereochemistry.



L12 ANSWER 2 OF 7 USPATFULL

ACCESSION NUMBER: 2002:340221 USPATFULL

TITLE: Photosensitive lithocholate derivative and chemically amplified photoresist composition containing the same  
 INVENTOR(S): Kim, Hyun-woo, Seongnam, KOREA, REPUBLIC OF  
 Lee, Sook, Seoul, KOREA, REPUBLIC OF  
 Woo, Sang-gyun, Suwon, KOREA, REPUBLIC OF

PATENT ASSIGNEE(S): Samsung Electronics Co., Ltd., Suwon, KOREA, REPUBLIC OF (non-U.S. corporation)

	NUMBER	KIND	DATE
PATENT INFORMATION:	US 6497987	B1	20021224
APPLICATION INFO.:	US 2000-662653		20000914 (9)

	NUMBER	DATE
PRIORITY INFORMATION:	KR 1999-39337	19990914
DOCUMENT TYPE:	Utility	
FILE SEGMENT:	GRANTED	
PRIMARY EXAMINER:	Baxter, Janet	
ASSISTANT EXAMINER:	Lee, Sin J.	
LEGAL REPRESENTATIVE:	Volentine Francos, PLLC	
NUMBER OF CLAIMS:	19	
EXEMPLARY CLAIM:	9	
NUMBER OF DRAWINGS:	0 Drawing Figure(s); 0 Drawing Page(s)	
LINE COUNT:	606	

CAS INDEXING IS AVAILABLE FOR THIS PATENT.

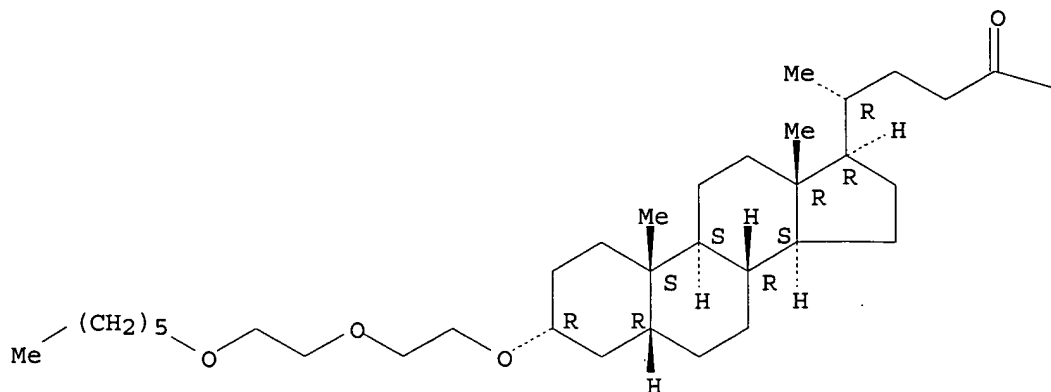
IT 340711-34-4P 340711-46-8P

(photosensitive lithocholate for chem. amplified photoresist)

RN 340711-34-4 USPATFULL

CN Cholan-24-oic acid, 3-[2-[2-(hexyloxy)ethoxy]ethoxy]-, 1,1-dimethylethyl ester, (3.alpha.,5.beta.)- (9CI) (CA INDEX NAME)

Absolute stereochemistry.

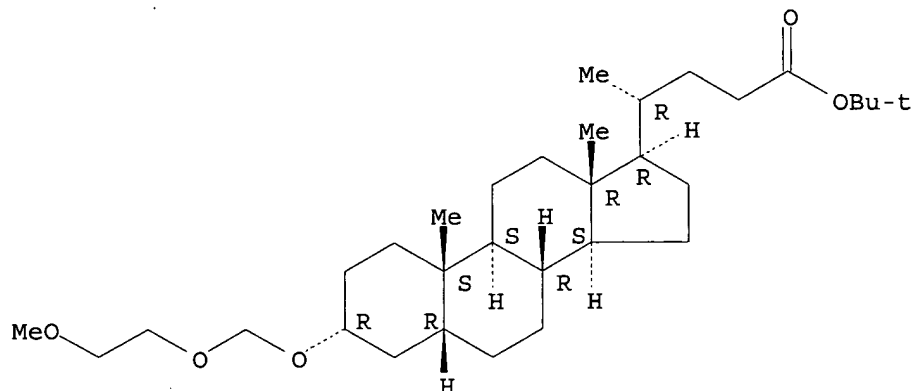


— OBU-t

RN 340711-46-8 USPATFULL

CN Cholan-24-oic acid, 3-[(2-methoxyethoxy)methoxy]-, 1,1-dimethylethyl ester, (3.alpha.,5.beta.)- (9CI) (CA INDEX NAME)

Absolute stereochemistry.



L12 ANSWER 3 OF 7 CAPLUS COPYRIGHT 2003 ACS

DUPLICATE 2

ACCESSION NUMBER: 2001:369721 CAPLUS

DOCUMENT NUMBER: 134:374048

TITLE: Photosensitive lithocholate and chemically amplified photoresist composition containing it

INVENTOR(S): Kim, Hyun Woo; Lee, Sook; Woo, Sang Gyun

PATENT ASSIGNEE(S): Samsung Electronics Co., Ltd., S. Korea

SOURCE: Jpn. Kokai Tokkyo Koho, 12 pp.

CODEN: JKXXAF

DOCUMENT TYPE: Patent

LANGUAGE: Japanese

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO.

KIND DATE

APPLICATION NO. DATE

JP 2001139595	A2	20010522	JP 2000-280371	20000914
US 6497987	B1	20021224	US 2000-662653	20000914

PRIORITY APPLN. INFO.: KR 1999-39337 A 19990914

IT 340711-34-4P 340711-46-8P

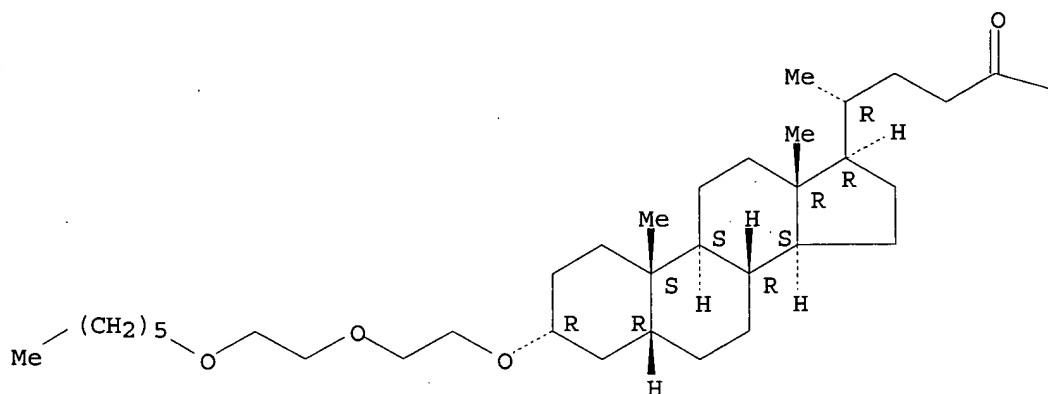
RL: PNU (Preparation, unclassified); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)  
 (photosensitive lithocholate for chem. amplified photoresist)

RN 340711-34-4 CAPLUS

CN Cholan-24-oic acid, 3-[2-[2-(hexyloxy)ethoxy]ethoxy]-, 1,1-dimethylethyl ester, (3.alpha.,5.beta.)- (9CI) (CA INDEX NAME)

Absolute stereochemistry.

PAGE 1-A



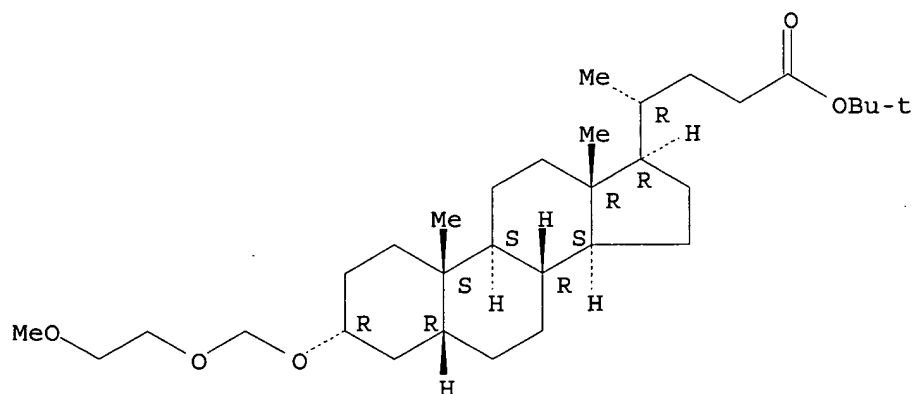
PAGE 1-B

OBu-t

RN 340711-46-8 CAPLUS

CN Cholan-24-oic acid, 3-[(2-methoxyethoxy)methoxy]-, 1,1-dimethylethyl ester, (3.alpha.,5.beta.)- (9CI) (CA INDEX NAME)

Absolute stereochemistry.



ACCESSION NUMBER: 97:54217 USPATFULL  
 TITLE: Modified bile acids process for their preparation and their use  
 INVENTOR(S): Wess, Gunther, Erlensee, Germany, Federal Republic of  
 Ehnsen, Alfons, Buttelborn, Germany, Federal Republic of  
 Kramer, Werner, Mainz, Germany, Federal Republic of  
 Bock, Klaus, Hattersheim, Germany, Federal Republic of  
 PATENT ASSIGNEE(S): Hoechst Aktiengesellschaft, Frankfurt am Main, Germany,  
 Federal Republic of (non-U.S. corporation)

	NUMBER	KIND	DATE
PATENT INFORMATION:	US 5641767		19970624
APPLICATION INFO.:	US 1995-525231		19950912 (8)

	NUMBER	DATE
PRIORITY INFORMATION:	DE 1994-4432708	19940914
DOCUMENT TYPE:	Utility	
FILE SEGMENT:	Granted	
PRIMARY EXAMINER:	Prior, Kimberly J.	
LEGAL REPRESENTATIVE:	Finnegan, Henderson, Farabow, Garrett & Dunner, L.L.P.	
NUMBER OF CLAIMS:	6	
EXEMPLARY CLAIM:	1	
LINE COUNT:	826	
CAS INDEXING IS AVAILABLE FOR THIS PATENT.		

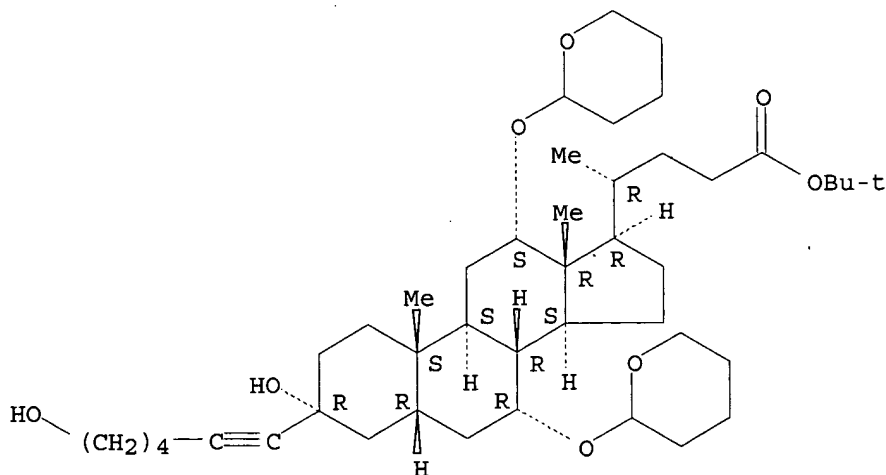
IT 176256-27-2P

(prepn. of modified bile acids for use as hypolipemics)

RN 176256-27-2 USPATFULL

CN Cholan-24-oic acid, 3-hydroxy-3-(6-hydroxy-1-hexynyl)-7,12-bis[(tetrahydro-2H-pyran-2-yl)oxy]-, 1,1-dimethylethyl ester,  
 (3.alpha.,5.beta.,7.alpha.,12.alpha.)- (9CI) (CA INDEX NAME)

Absolute stereochemistry.



L12 ANSWER 5 OF 7 CAPLUS COPYRIGHT 2003 ACS

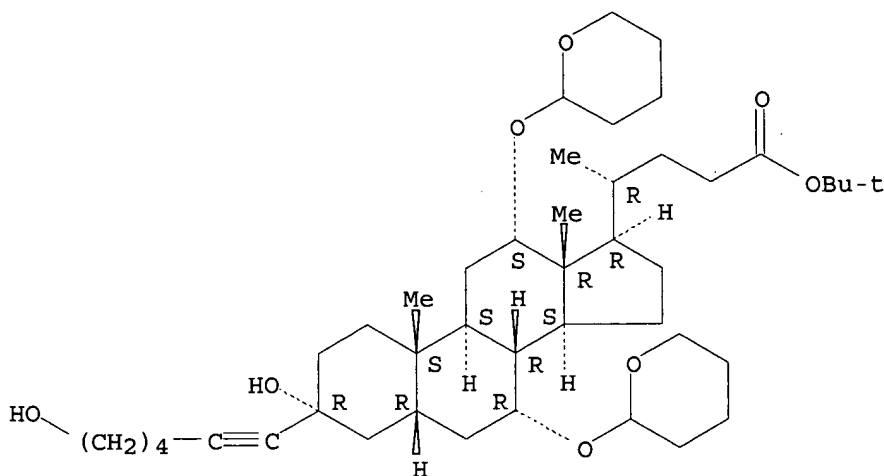
DUPLICATE 3

ACCESSION NUMBER: 1996:284486 CAPLUS  
 DOCUMENT NUMBER: 124:317606  
 TITLE: Modified bile acids for use as hypolipemics  
 INVENTOR(S): Wess, Guenther; Ehnsen, Alfons; Kramer, Werner; Bock,  
 Klaus  
 PATENT ASSIGNEE(S): Hoechst A.-G., Germany  
 SOURCE: Eur. Pat. Appl., 30 pp.

CODEN: EPXXDW  
 DOCUMENT TYPE: Patent  
 LANGUAGE: German  
 FAMILY ACC. NUM. COUNT: 1  
 PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
EP 702026	A2	19960320	EP 1995-114107	19950908
EP 702026	A3	19960724		
R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IE, IT, LI, LU, NL, PT, SE				
DE 4432708	A1	19960321	DE 1994-4432708	19940914
US 5641767	A	19970624	US 1995-525231	19950912
JP 08099991	A2	19960416	JP 1995-234891	19950913
PRIORITY APPLN. INFO.:			DE 1994-4432708	19940914
OTHER SOURCE(S):	MARPAT 124:317606			
IT	176256-27-2P			
RL:	RCT (Reactant); SPN (Synthetic preparation); PREP (Preparation); RACT (Reactant or reagent)			
	(prepn. of modified bile acids for use as hypolipemics)			
RN	176256-27-2 CAPLUS			
CN	Cholan-24-oic acid, 3-hydroxy-3-(6-hydroxy-1-hexynyl)-7,12-bis[(tetrahydro-2H-pyran-2-yl)oxy]-, 1,1-dimethylethyl ester, (3.alpha.,5.beta.,7.alpha.,12.alpha.)- (9CI) (CA INDEX NAME)			

Absolute stereochemistry.

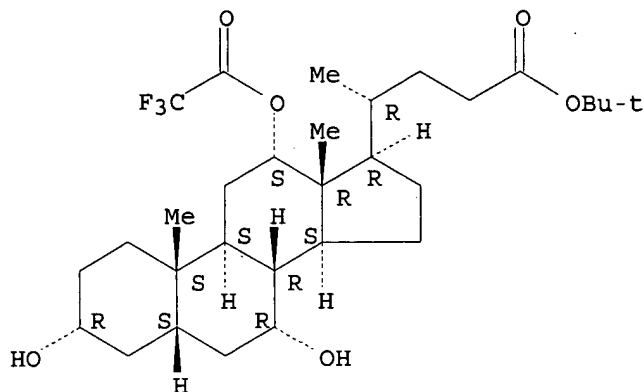


L12 ANSWER 6 OF 7 CAPLUS COPYRIGHT 2003 ACS DUPLICATE 4  
 ACCESSION NUMBER: 1996:10570 CAPLUS  
 DOCUMENT NUMBER: 124:145704  
 TITLE: Synthesis of cyclocholesterol-capped porphyrins  
 AUTHOR(S): Bonar-Law, Richard P.; Sanders, Jeremy K. M.  
 CORPORATE SOURCE: Cambridge Cent. Mol. Recognition, Univ. Chemical Lab., Cambridge, CB2 1EW, UK  
 SOURCE: Journal of the Chemical Society, Perkin Transactions 1: Organic and Bio-Organic Chemistry (1995), (24), 3085-96  
 CODEN: JCPRB4; ISSN: 0300-922X  
 PUBLISHER: Royal Society of Chemistry  
 DOCUMENT TYPE: Journal  
 LANGUAGE: English  
 IT 130781-88-3  
 RL: RCT (Reactant); RACT (Reactant or reagent)  
 (prepn. of cyclocholesterol-capped porphyrins)



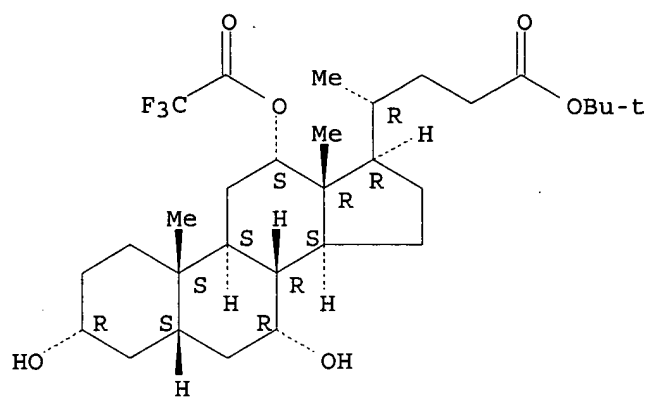
RN 130781-88-3 CAPLUS  
 CN Cholan-24-oic acid, 3,7-dihydroxy-12-[(trifluoroacetyl)oxy]-,  
 1,1-dimethylethyl ester, (3.alpha.,5.beta.,7.alpha.,12.alpha.)- (9CI) (CA  
 INDEX NAME)

Absolute stereochemistry.



L12 ANSWER 7 OF 7 CAPLUS COPYRIGHT 2003 ACS DUPLICATE 5  
 ACCESSION NUMBER: 1991:6933 CAPLUS  
 DOCUMENT NUMBER: 114:6933  
 TITLE: New procedures for selectively protected cholic acid  
 derivatives. Regioselective protection of the  
 12.alpha.-hydroxy group, and tert-butyl esterification  
 of the carboxyl group  
 AUTHOR(S): Bonar-Law, Richard P.; Davis, Anthony P.; Sanders,  
 Jeremy K. M.  
 CORPORATE SOURCE: Dep. Chem., Trinity Coll., Dublin, UK  
 SOURCE: Journal of the Chemical Society, Perkin Transactions  
 1: Organic and Bio-Organic Chemistry (1972-1999)  
 (1990), (8), 2245-50  
 CODEN: JCPRB4; ISSN: 0300-922X  
 DOCUMENT TYPE: Journal  
 LANGUAGE: English  
 OTHER SOURCE(S): CASREACT 114:6933  
 IT 130781-88-3P  
 RL: RCT (Reactant); SPN (Synthetic preparation); PREP (Preparation); RACT  
 (Reactant or reagent)  
 (prepn. and partial O-acetylation of)  
 RN 130781-88-3 CAPLUS  
 CN Cholan-24-oic acid, 3,7-dihydroxy-12-[(trifluoroacetyl)oxy]-,  
 1,1-dimethylethyl ester, (3.alpha.,5.beta.,7.alpha.,12.alpha.)- (9CI) (CA  
 INDEX NAME)

Absolute stereochemistry.



2003

L11 12 S L10  
L12 7 DUPLICATE REMOVE L11 (5 DUPLICATES REMOVED)  
L13 89 S L5  
L14 46 DUPLICATE REMOVE L13 (43 DUPLICATES REMOVED)  
L15 43 S L14 NOT L12  
L16 5 S L15 AND (PHOTORESIST OR RESIST)

=> d l16 1-5 ibib hitstr abs

L16 ANSWER 1 OF 5 CAPLUS COPYRIGHT 2003 ACS

ACCESSION NUMBER: 2002:566567 CAPLUS

DOCUMENT NUMBER: 137:132103

TITLE: Positive-working **photoresist** composition

INVENTOR(S): Fujimori, Toru

PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan

SOURCE: Jpn. Kokai Tokkyo Koho, 93 pp.

CODEN: JKXXAF

DOCUMENT TYPE: Patent

LANGUAGE: Japanese

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

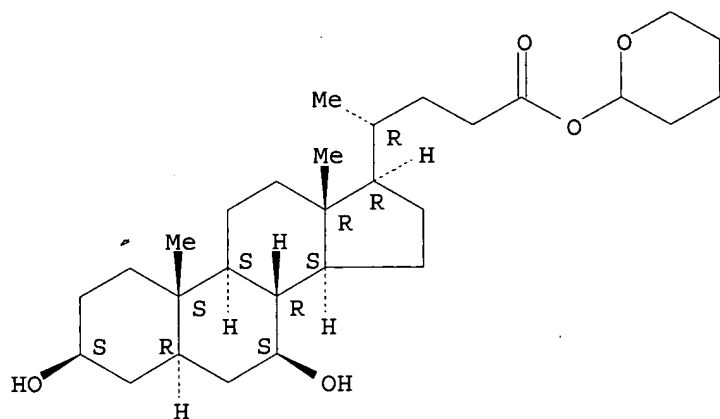
PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2002214787	A2	20020731	JP 2001-13298	20010122
PRIORITY APPLN. INFO.: IT 444311-25-5			JP 2001-13298	20010122

RL: TEM (Technical or engineered material use); USES (Uses)  
(compd. having an acid-sensitive group in pos.-working  
**photoresist** compn.)

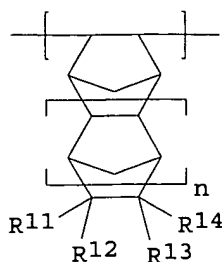
RN 444311-25-5 CAPLUS

CN Cholan-24-oic acid, 3,7-dihydroxy-, tetrahydro-2H-pyran-2-yl ester,  
(3.beta.,5.alpha.,7.beta.)- (9CI) (CA INDEX NAME)

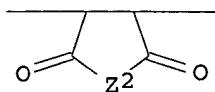
Absolute stereochemistry.



GI



I



II

AB The title compn. contains a light- or radiation-sensitive acid generator, a resin increasing soly. rate in an alkali developer by an acid, and a compd. having an acid-sensitive group, wherein the resin has repeating group I (R11-14 = acid-sensitive group, H, halo, cyano, etc.; n = 0, 1), II (Z2 = -O-, -N(R41)-; R41 = H, OH, alkyl, etc.), and [CH<sub>2</sub>-C(R91)(CO-X5-B-R92)] (R91 = H, lower alkyl, halo, -CN; X5 = -O-, -S-, -NR93; R93 = H, chain or cyclic alkyl; B = single bond, connecting group; R92 = H, chain or cyclic alkyl, alkoxy, carboxy, etc.) and wherein the compd. having the acid-sensitive group generates a group, which is sol. in the alkali developer or more sol. in the alkali developer before the acid reaction. The compn. shows the improved stability during the post exposure delay (PED).

L16 ANSWER 2 OF 5 CAPLUS COPYRIGHT 2003 ACS

ACCESSION NUMBER: 2000:209759 CAPLUS

DOCUMENT NUMBER: 132:243958

TITLE: Chemically amplified positive **photoresist** composition

INVENTOR(S): Park, Joo-hyeon; Seo, Dong-chul; Park, Sun-yi; Kim, Seong-ju

PATENT ASSIGNEE(S): Korea Kumho Petrochemical Co. Ltd., S. Korea

SOURCE: Eur. Pat. Appl., 16 pp.

CODEN: EPXXDW

DOCUMENT TYPE: Patent

LANGUAGE: English

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
EP 989458	A2	20000329	EP 1999-307323	19990915
EP 989458	A3	20000517		
R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, SI, LT, LV, FI, RO				
US 6268106	B1	20010731	US 1999-337434	19990621
JP 2000098615	A2	20000407	JP 1999-202428	19990716
JP 3040998	B2	20000515		

PRIORITY APPLN. INFO.: KR 1998-39372 A 19980923

OTHER SOURCE(S): MARPAT 132:243958

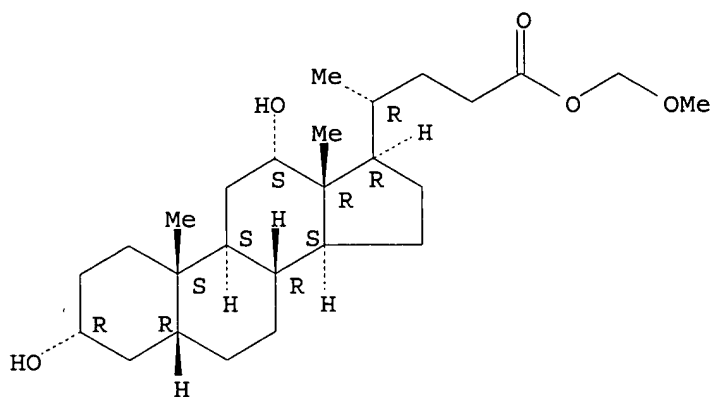
IT 261778-12-5P

RL: SPN (Synthetic preparation); PREP (Preparation)  
(prepn. of cholic acid deriv. for chem. amplified pos.  
**photoresist** compn. for sub-micro lithog.)

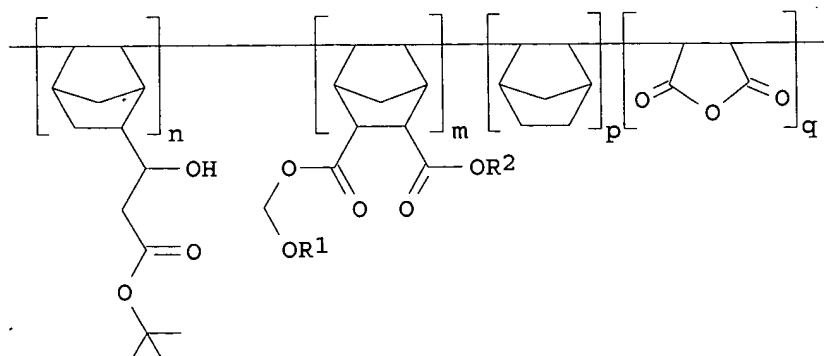
RN 261778-12-5 CAPLUS

CN Cholan-24-oic acid, 3,12-dihydroxy-, methoxymethyl ester,  
(3.alpha.,5.beta.,12.alpha.)- (9CI) (CA INDEX NAME)

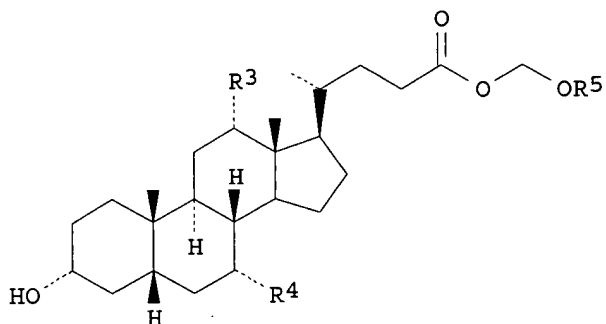
Absolute stereochemistry.



GI



I



II

AB Disclosed is a chem. amplification pos. amplification which can be formed into **resist** patterns much improved in transparency, photosensitivity and resolu. and is suitable to KrF and ArF excimer lasers, enabling a sub-micro lithog. process to be as exquisite as 0.2  $\mu$ m or less. This compn. is based on a copolymer I (R1 and R2 = alkyl or cyclic alkyl groups, ranging, in polystyrene-reduced wt. av. mol. wt., from 3,000 to 50,000 with a mol. wt. distribution (Mw/Mn) of 1.0 to 2.0), and a low mol. wt. compd. II (R3 and R4 = H or OH; R5, a low alkyl group, a norbornene or an adamantane or a decalin contg. alkyl group).

L16 ANSWER 3 OF 5 CAPLUS COPYRIGHT 2003 ACS

ACCESSION NUMBER: 1999:460321 CAPLUS

DOCUMENT NUMBER: 131:108922

TITLE: Radiation-sensitive resin composition

INVENTOR(S): Kajita, Toru; Suwa, Mitsuhiro; Iwasawa, Haruo;

PATENT ASSIGNEE(S): Yamamoto, Masafumi  
 SOURCE: JSR Corporation, Japan  
 Eur. Pat. Appl., 49 pp.  
 CODEN: EPXXDW  
 DOCUMENT TYPE: Patent  
 LANGUAGE: English  
 FAMILY ACC. NUM. COUNT: 1  
 PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
EP 930541	A1	19990721	EP 1999-100718	19990115
R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, SI, LT, LV, FI, RO				
JP 11202491	A2	19990730	JP 1998-18290	19980116
JP 11265067	A2	19990928	JP 1998-270685	19980925
US 6180316	B1	20010130	US 1999-231762	19990115
PRIORITY APPLN. INFO.:			JP 1998-18290	A 19980116
			JP 1998-18291	A 19980116
			JP 1998-270685	A 19980925

OTHER SOURCE(S): MARPAT 131:108922

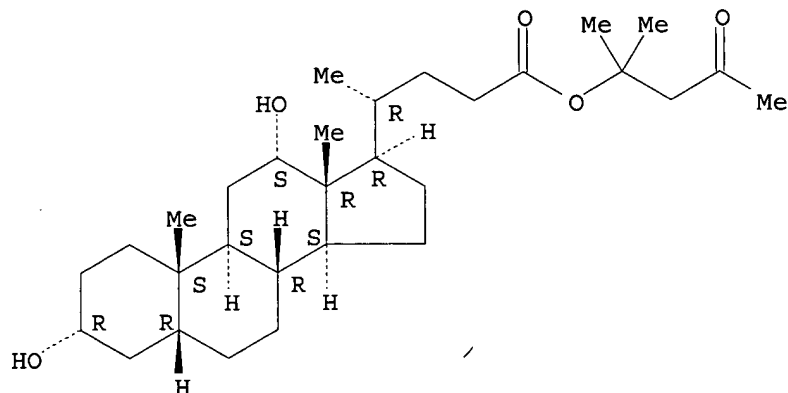
IT **231296-52-9P**

RL: SPN (Synthetic preparation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)  
 (prepn. and use in chem. amplified **photoresists** contg. norbornene copolymers)

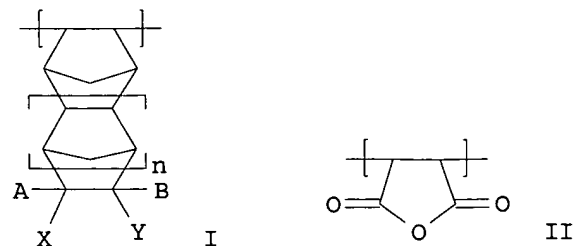
RN 231296-52-9 CAPLUS

CN Cholan-24-oic acid, 3,12-dihydroxy-, 1,1-dimethyl-3-oxobutyl ester,  
 (3.alpha.,5.beta.,12.alpha.)- (9CI) (CA INDEX NAME)

Absolute stereochemistry.



GI



AB A radiation-sensitive resin compn. useful as a chem. amplified **resist** comprises (A) a polymer contg. (a) a recurring unit of the formula I (A, B = H or an acid-decomposable org. group having .ltoreq.20 C atoms which dissocks. in the presence of an acid and produces an acidic functional group provided that either one of A and B is the acid-decomposable org. group; X, Y = H or alkyl having 1-4 C atoms; n = 0 or 1) or a recurring unit of the formula I and a recurring unit of the formula II and (b) a recurring unit which is derived from a monomer having at least two polymerizable carbon-carbon double bonds by cleavage of the carbon-carbon double bonds, wherein the monomer has, in addn. to said at least two polymerizable carbon-carbon double bonds, at least one acid-decomposable divalent group of the formula -CO<sub>2</sub>C(R<sub>1</sub>)(R<sub>2</sub>)- or -OCOC(R<sub>3</sub>)(R<sub>4</sub>)- (R<sub>1</sub>-4 = alkyl having 1-5 C atoms), said at least two polymerizable carbon-carbon double bonds being linked via the acid-decomposable divalent group and (B) a photoacid generator.

REFERENCE COUNT: 5 THERE ARE 5 CITED REFERENCES AVAILABLE FOR THIS RECORD. ALL CITATIONS AVAILABLE IN THE RE FORMAT

L16 ANSWER 4 OF 5 USPATFULL

ACCESSION NUMBER: 2001:121213 USPATFULL

TITLE: Chemically amplified positive **photoresist** composition

INVENTOR(S): Park, Joo-Hyeon, Taejeon, Korea, Republic of  
Seo, Dong-Chul, Taejeon, Korea, Republic of  
Park, Sun-Yi, Taejeon, Korea, Republic of  
Kim, Seong-Ju, Taejeon, Korea, Republic of

PATENT ASSIGNEE(S): Korea Kumho Petrochemical Co., Ltd., Seoul, Korea, Republic of (non-U.S. corporation)

	NUMBER	KIND	DATE
PATENT INFORMATION:	US 6268106	B1	20010731
APPLICATION INFO.:	US 1999-337434		19990621 (9)

	NUMBER	DATE
PRIORITY INFORMATION:	KR 1998-39372	19980923
DOCUMENT TYPE:	Utility	
FILE SEGMENT:	GRANTED	
PRIMARY EXAMINER:	Baxter, Janet	
ASSISTANT EXAMINER:	Ashton, Rosemary	
LEGAL REPRESENTATIVE:	Harrison & Egbert	
NUMBER OF CLAIMS:	4	
EXEMPLARY CLAIM:	1	
LINE COUNT:	769	

CAS INDEXING IS AVAILABLE FOR THIS PATENT.

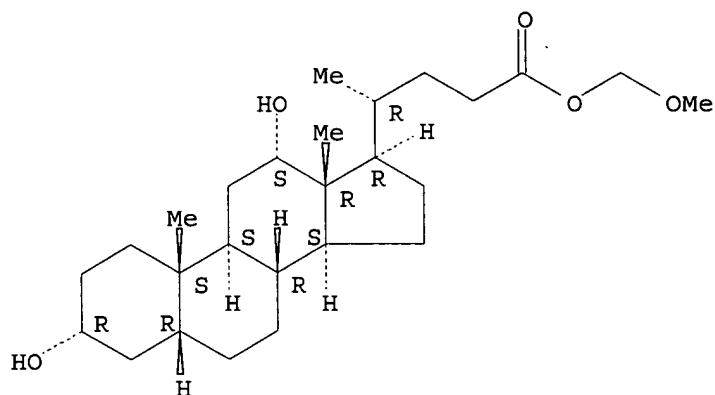
IT 261778-12-5P

(prepn. of cholic acid deriv. for chem. amplified pos. photoresist compn. for sub-micro lithog.)

RN 261778-12-5 USPATFULL

CN Cholan-24-oic acid, 3,12-dihydroxy-, methoxymethyl ester, (3.alpha.,5.beta.,12.alpha.)- (9CI) (CA INDEX NAME)

Absolute stereochemistry.



AB A chemical amplification positive amplification which can be formed into **resist** patterns much improved in transparency, photosensitivity and resolution and is suitable to KrF and ArF excimer lasers, enabling a submicrolithography process to be as exquisite as 0.2 .mu.m or less. This composition is based on a copolymer of the formula I, ranging, in polystyrene-reduced weight average molecular weight, from 3,000 to 50,000 with a molecular weight distribution (M.sub.w /M.sub.n) of 1.0 to 2.0, and a low molecular weight compound of the formula VI: ##STR1##

CAS INDEXING IS AVAILABLE FOR THIS PATENT.

L16 ANSWER 5 OF 5 USPATFULL

ACCESSION NUMBER: 2001:14174 USPATFULL  
 TITLE: Radiation sensitive resin composition  
 INVENTOR(S): Kajita, Toru, Mie, Japan  
 Suwa, Mitsuhiro, Mie, Japan  
 Iwasawa, Haruo, Mie, Japan  
 Yamamoto, Masafumi, Mie, Japan  
 PATENT ASSIGNEE(S): JSR Corporation, Tokyo, Japan (non-U.S. corporation)

	NUMBER	KIND	DATE
PATENT INFORMATION:	US 6180316	B1	20010130
APPLICATION INFO.:	US 1999-231762		19990115 (9)

	NUMBER	DATE
PRIORITY INFORMATION:	JP 1998-18290	19980116
	JP 1998-18291	19980116
	JP 1998-270685	19980925

DOCUMENT TYPE: Utility  
 FILE SEGMENT: Granted  
 PRIMARY EXAMINER: Chu, John S.  
 LEGAL REPRESENTATIVE: Oblon, Spivak, McClelland, Maier & Neustadt, P.C.  
 NUMBER OF CLAIMS: 21  
 EXEMPLARY CLAIM: 1,3  
 LINE COUNT: 2380

CAS INDEXING IS AVAILABLE FOR THIS PATENT.

IT 231296-52-9P

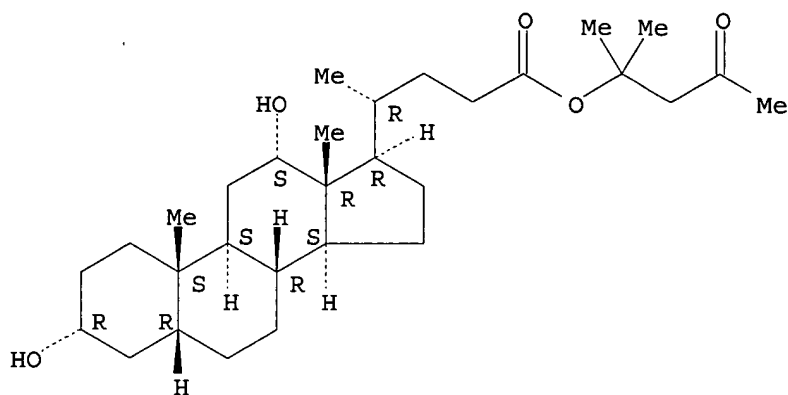
(prepn. and use in chem. amplified photoresists contg. norbornene copolymers)

RN 231296-52-9 USPATFULL

CN Cholan-24-oic acid, 3,12-dihydroxy-, 1,1-dimethyl-3-oxobutyl ester, (3.alpha.,5.beta.,12.alpha.)- (9CI) (CA INDEX NAME)

Absolute stereochemistry.





- AB A radiation-sensitive resin composition which comprises,
- (A) a polymer containing,
- (a) a recurring unit (I) of the following formula (1): ##STR1##
- or a recurring unit (I) of the formula (1) and a recurring unit (II) of the following formula (2), ##STR2##
- and
- (b) a recurring unit (III) which is derived from a monomer having at least two polymerizable carbon--carbon double bonds by cleavage of the carbon--carbon double bonds, wherein the monomer has, in addition to said at least two polymerizable carbon--carbon double bonds, at least one acid-decomposable divalent group of the following formula (3) or (4), ##STR3##
- said at least two polymerizable carbon--carbon double bonds being linked via the least one acid-decomposable divalent group of the formula (3) or (4), and
- (B) a photoacid generator.

CAS INDEXING IS AVAILABLE FOR THIS PATENT.